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(71)Applicant : FUJI PHOTO FILM CO LTD

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(54) PHOTSENSITIVE MATERIAL

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a photosensitive material having high sensitivity to the oscillation wavelength of a short-wavelength semiconductor laser, excellent in storage stability, developable with water or an aqueous solution or exhibiting good on-printing press developability by which the material is attached to a printing press as it is without developing and enables printing and ensuring further improved printing resistance and printing stain on a printed surface.

SOLUTION: The photosensitive material has an image recording layer containing (a) a compound having two or more blocked isocyanate groups in one molecule and (b) a compound which generates a di- or higher valent base when heated or irradiated with active radiation on a hydrophilic base. Preferably (c) a photothermal converting material is further contained.

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